



Docket No. 0760-0296P

15. (Amended) Use of said polyimide recited in claim 1 as a material for positive-type photolithography.

16. (Amended) A method for forming negative-type pattern of polyimide comprising coating a substrate with the polyimide recited in claim 1; selectively irradiating the polyimide with an actinic ray, the irradiated regions constituting a desired pattern; and developing the irradiated polyimide with an alkaline solution to dissolve the non-irradiated regions.

18. (Amended) Use of the polyimide recited in claim 1 as a material for negative-type photolithography.